SUPERCRITICAL CPD MEMS DRYER FOR 4" WAFERS

Autosamdri®-815B, Series C

UNPARALLELED VERSATILITY AND LOW LCO2 CONSUMPTION

tousimis



- The Autosamdri*-815B, Series C maintains tousimis* process quality and achieves a small facility foot print while utilizing an efficient closed loop refrigeration and waste alcohol collection design.*
- 35 years of tousimis* CPD experience enables smooth operation and precise control. HF Compatible Wafer Holders* and Chamber Inserts* are provided, allowing flexible CPD processing of various wafer sizes and die.



SUPERCRITICAL Autosamdri®-815B, Series C

Catalog# 8780D (Process Various Wafer Sizes up to 4in)

- 40% Less LCO2 Consumption.¹
- Process up to 5 wafers in Less than 1 hour.
- All inclusive Small Foot Print design.
- · Minimal installation Site Preparation required.
- On Site Start-Up and User Training included.²



Standard Accessories

Samdried™ Wafer

Airdried Wafer

FEATURES

- High efficiency internal closed loop refrigeration.*
 (22°C to operational in less than 3 minutes)!
- Post-Purge-Filter easily accessible for maintenance ease.*
- The patented internal SOTER" condenser* quietly captures and separates CO2 exhaust and waste alcohols.
- Unique chamber inserts* enable variance of chamber I.D. maximizing efficiency in LCO₂ consumption, process time, and providing multiple size wafer process capability!
- Process up to 5 x 4" wafers per process run. Also comes with additional HF Compatible Wafer Holders* to process 5 x 3", 5 x 2" diameter wafers or 5 x 10mm square die (tousimis* HF compatible Wafer Holders* may be used to etch and process your wafers minimizing handling).
- Chamber illumination with viewing window facilitates chamber status visualization.*
- · Microprocessor controller allows for completely automatic processing.*
- All internal surfaces are inert to CO₂ and ultrapure alcohols.
- · Repeatable operating parameters insuring "reproducibility" of results.
- Static pressure control module helps insure automatic safe pressure stability.
- Internal filtration system delivers clean LCO2 into process chamber down to 0.4µm.
- · Control panel LED's instantly indicate process mode at a glance.
- · Clean room static-free compatible design.
- All electronic components meet CE, UL and/or U.S. Military Specifications.

SPECIFICATIONS

- Cabinet: 17.25" (43.8cm) Width x 43" (109.2cm) Height x 29.25" (74.3cm) Depth
- System Set-Up Area Footprint: 24" (61.0cm) Width x 34" (86.4cm) Depth.
- Chamber size: 4.50" I.D. x 1.25" Depth / Chamber volume: 326 ml
- Temperature gauge range: -30°C to 60°C, Pressure gauge range: 0 to 2,000 psi
- 120V / 50-60Hz (Other voltage units also available. Please Inquire)
- LCO2 flow is precisely controlled through Micro Metering Valves with Vernier handles for adjustment ease.*

STANDARD ACCESSORIES

- LCO₂ High Pressure braided stainless steel inert Teflon* lined hose. 10ft (~ 3m) long for clean room operation (at a nominal charge, other lengths available upon request).
- LCO $_2$ external combination filter assembly (#8784) for water/oil/particulates (down to 0.5 μ m) pre-installed onto the chamber LCO $_2$ supply high-pressure hose.
- Tool set included for connecting LCO₂ chamber supply line
- Static free exhaust tubing for all exhaust outlets.
- Internal stainless and nickel scintered filtration systems incorporated to protect lines, wafers, and valves down to 0.4µm.
- Spare chamber O-rings (3), chamber lamps (2), and slo-blow fuses (2x3A and 2x8A).
- Complete wafer size process flexibility! 3 chamber inserts* enable 4.5" chamber I.D. reduction down to smaller chamber I.D. sizes for processing wafers and die from a range including: 4", 3", 2", and 1.25"! Allows for multiple wafer size drying.
- 4", 3", 2" diameter wafer holders and 10mm square die holders included. Holders are HF compatible and can hold up to 5 wafers or die each.
- 2 year warranty on all parts and labor. Free lifetime technical support consultations by our scientific staff.

Note: Actual delivered model or accessories may vary slightly, as advancements are constantly being applied.

¹ Compared with tousimis Autosamdri*-815B, Series B

² Available for most countries. Contact tousimis for details.

^{*} Most Automegasamdri® feature U.S. patents (#6,493,964, #6,678,968) or patents pending.